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U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
<i>RLK</i>	5,569,615	10/29/96	Yamazaki et al.	437	43	
<i>RLK</i>	4,780,424	10/25/88	Holler et al.	437	43	
<i>RLK</i>	4,861,730	08/29/89	Hsia et al.	437	43	
<i>RLK</i>	5,114,876	5/19/92	Weiner	437	174	
<i>RLK</i>	5,180,690	1/19/93	Czubatyj et al.	437	165	12/14/88
<i>RLK</i>	5,158,903	10/27/92	Hori et al.	437	44	

FOREIGN PATENT DOCUMENTS

Document Number	Date	Country	Class	Subclass	Translation Yes No	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>RLK</i>	Sameshima et al., "XeCl excimer laser annealing used to fabricate poly-si TFTs", Mat. Res. Soc. Symp. Proc., Vol. 71, 1986, pp. 435-440
<i>RLK</i>	Corey et al., "A shallow junction submicrometer PMOS process without high temperature anneals", IEEE electron device letters, Vol. 9, No. 10, Oct. 1988, pp. 542-544
<i>RLK</i>	"Fabrication of Submicrometer MOSFET's Using Gas Immersion Laser Doping (GILD)", IEEE Electron Device Letters, Vol. EDL-7, No. 7, pp. 440-442

Examiner *G. MUNSON*Date Considered *30 DECEMBER 1997*

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.